



PATENT
Atty. Dkt. AMAT/3049/ISM/ISMB/SB

GAV 1765

#9/B
10/14/00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Cohen et al.

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Serial No.: 09/206,027

Group Art Unit: 1765

RECEIVED

Filed: December 4, 1998

Examiner: Lan Vinh

For: Plasma Preclean With Argon, Helium, and Hydrogen Gases

CERTIFICATE OF MAILING

Assistant Commissioner for Patents
Washington, D.C. 20231

CERTIFICATE OF MAILING
37 C.F.R. 1.8

Dear Sir:

RESPONSE TO OFFICE ACTION DATED JULY 5, 2000

In response to the Office Action dated July 5, 2000, having a shortened statutory period for response set to expire on October 5, 2000, please enter the following amendments and reconsider the claims pending in the application for reasons discussed below. Please charge the amount of \$204.00 and any additional fees necessary for one independent claim in excess of three and a net of five additional claims in excess of twenty to Deposit Account No. 20-0782/AMAT/3049/ISM/ISMB/DV of Thomason, Moser & Patterson, L.L.P.

IN THE CLAIMS:

Please cancel claims 2 and 9 without prejudice, and amend the claims as follows:

1. (Amended) A method for processing a substrate in a processing chamber, comprising exposing a patterned substrate surface to a plasma [comprising] consisting of argon, helium and hydrogen [in a processing chamber], wherein the plasma comprises less than about 75% by volume of argon.